Plasma processes under low and atmospheric pressure.

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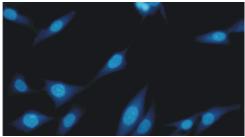
Department of Macromolecular Physics

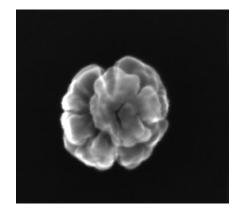
Outline

- Who we are?
- What is plasma?



- How can be plasma used for surface modification?
 - Plasma treatment of polymers
 - Sterilization
- Thin film deposition
- Nanostructured coatings
- Nanoparticles





Who we are?

1348 Universitas Carolina



Faculty of Mathematics and Physics

~ 1000 student of Physics

14 departments

Department of Macromolecular physics

Charles University in Prague has more than 7,500 employees

Over 51,000 students 17 faculties

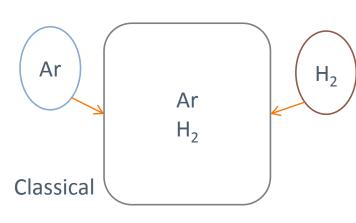


5 researchers 8 students (6 PhD)



What is plasma?

• Ar + H₂ \rightarrow ?



Plasma main: Ar, H₂ $10^{-3}-10^{-6}$: H, H^{*}, Ar^{*}, Ar_m^{*}, Ar⁺, Ar²⁺, H⁺, H₂⁺, H₃⁺, ArH⁺, ... e⁻

No thermal equilibrium! $T_n \sim 0.03 eV, T_i \sim 0.1 eV, T_e \sim 1 eV + fast (>10 eV) ions and$ **electrons**

Table 2 Reactions taken into account in the Monte Carlo models

Elastic scattering

Excitation to the metastable levels

Ionization

Electron Monte Carlo model—	
Elastic scattering	$e^- + Ar \rightarrow e^- + Ar$
Ionization	$e^- + Ar \rightarrow e^- + Ar^+ + e^-$
Total excitation (including up to the Ar metastable levels)	$e^- + Ar \rightarrow e^- + Ar^*$ (incl. Ar_m^*)
Ionization from the Ar metastable levels	$e^- + Ar_m^* \rightarrow e^- + Ar^+ + e^-$
Total excitation from the Ar metastable levels	$e^- + Ar_m^* \rightarrow e^- + Ar^*$
Elastic scattering	$e^- + H_2 \rightarrow e^- + H_2$
Total vibrational excitation	$e^{-} + H_{2} \rightarrow e^{-} + H_{2}^{*}(v)$
Total electron excitation to singlet states	$e^{-} + H_{2} \rightarrow e^{-} + H_{2}^{*}$ (s)
Total electron excitation to triplet states, followed by dissociation	$e^- + H_2 \rightarrow e^- + H_2^* (t) \rightarrow e^- + H + H$
Ionization	$e^{-} + H_2 \rightarrow e^{-} + H_2^{+} + e^{-}$
Dissociative ionization	$e^- + H_2 \rightarrow e^- + H^+ + H + e^-$
Total excitation	$e^- + H \rightarrow e^- + H^*$
Ionization	$e^- + H \rightarrow e^- + H^+ + e^-$
Ar ⁺ Monte Carlo model—	
Elastic (isotropic) scattering	$Ar^+ + Ar \rightarrow Ar^+ + fast Ar$
Elastic scattering in backward direction (or so-called "symmetric charge transfer")	$Ar^+ + Ar \rightarrow fast Ar + slow Ar^+$
Ionization	$Ar^+ + Ar \rightarrow Ar^+ + Ar^+ + e^-$
Excitation to the metastable levels	$Ar^+ + Ar \rightarrow Ar^+ + Ar_m^*$
H-atom transfer	$Ar^+ + H_2 \rightarrow ArH^+ + H$
Asymmetric charge transfer	$Ar^+ + H_2 \rightarrow fast Ar + H_2^+$
ArH ⁺ Monte Carlo model—	1 1
Elastic scattering	$ArH^+ + Ar \rightarrow ArH^+ + fast Ar$
Collision-induced dissociation	$ArH^+ + Ar \rightarrow fast Ar + H^+ + Ar$
Collision-induced dissociation	$ArH^+ + Ar \rightarrow fast Ar^+ + H + Ar$
	$ArH^+ + H_2 \rightarrow ArH^+ + fast H_2$
Elastic scatteri Proton transfer Advantage:	$ArH^+ + H_2 \rightarrow fast Ar + H_3^+$
H ⁺ Monte Carlo model—	
Elastic scattering	$H^+ + Ar \rightarrow H^{\pm} + fast Ar$
Asymmetric CR icch physics and	chemistry!
Symmetric charge transfer	
Total vibrational excitation	$H^+ + H_2 \rightarrow H^+ + H_2^*$ (v)
Elastic scattering	$H^+ + H_2 \rightarrow H^+ + fast H_2$
Asymmetric charge transfer	$H^+ + H_2^- \rightarrow fast H + H_2^+$
H ₂ ⁺ Monte Carlo model—	
Proton transfer	$H_2^+ + Ar \rightarrow H + ArH^+$
Asymmetric Disadvantage:	$H_2^+ + Ar \rightarrow fast H_2 + Ar^+$
Proton transfer I Sauvallage.	$H_2^+ + H_2 \rightarrow H + H_3^+$
Symmetric charge transfer	$H_2^+ + H_2 \rightarrow fast H_2 + H_2^+$
H_3^+ Monte Carle model—	
H ^o Monte C Rick- Elastic scatter Rich physics and	chemistry
Proton transfer	H_3 + AI \rightarrow fast H_2 + slow JH
Charge transfer + dissociation	H_3^+ + Ar \rightarrow fast H_2 + fast H + slow Ar
Collision-induced dissociation	$H_3^+ + Ar \rightarrow fast H^+ + fast H_2 + slow A$
Collision-induced dissociation	$H_3^+ + Ar \rightarrow fast H_2^+ + fast H + slow A$
Elastic scattering	$H_3^+ + H_2 \rightarrow H_3^+ + fast H_2$
Proton transfer	$H_3^+ + H_2 \rightarrow fast H_2 + slow H_3^+$
Proton transfer + dissociation	$H_3^+ + H_2 \rightarrow fast H_2 + slow H_2 + slow I$
Proton transfer + dissociation	$H_3^+ + H_2 \rightarrow fast H_2 + slow H + slow H$
Charge transfer + dissociation	$H_3^+ + H_2 \rightarrow fast H_2 + fast H + slow H$
Collision-induced dissociation	$H_3^+ + H_2 \rightarrow fast H_2^+ + fast H + slow H_2^+$
Collision-induced dissociation	$H_3^+ + H_2^- \rightarrow fast H^+ + fast H_2 + slow I$
Collision-induced dissociation	$H_3^+ + H_2 \rightarrow fast H^+ + 2 fast H + slow$
Fast Ar ⁰ Monte Carlo model—	

fast Ar + slow Ar \rightarrow fast Ar + fast Ar fast Ar + slow Ar \rightarrow fast Ar + Ar⁺ + e⁻ fast Ar + slow Ar \rightarrow fast Ar + Ar_m*

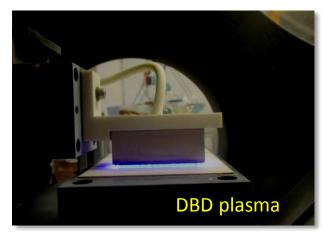


What is plasma?

Low pressure plasma



Atmospheric pressure plasma



Plasma is a complex mixture of electron, ions, neutrals, radicals, excited species.Plasma emits radiation in wide spectral range.

Plasma interacts with solid surfaces and may change their properties (chemical composition, morphology, bioresponsive properties etc.)



What is plasma?

Plasma is a complex mixture of electron, ions, neutrals, radicals, excited species.Plasma emits radiation in wide spectral range.

Surface modification Surface cleaning Surface sterilization

Deposition of thin films Deposition of nanostructured coatings Deposition of nanocompoiste materials



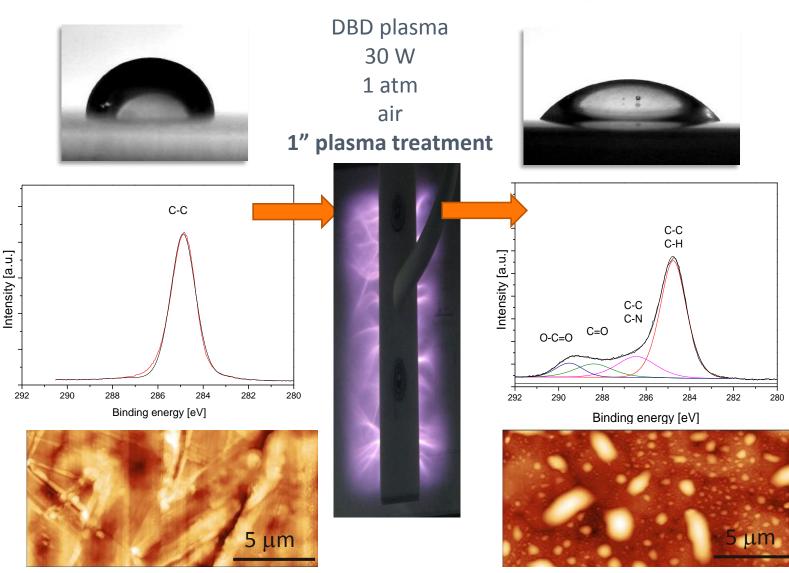
Biomedical applications

Biomedical applications Photovoltaic, Fuel cells Barrier and protective coatings

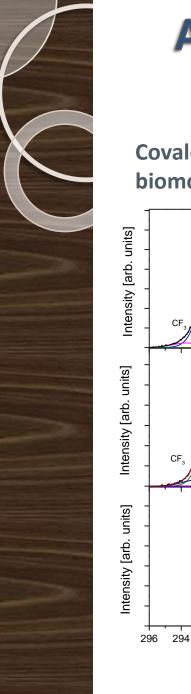
Advantages:

Possibility to process virtually any substrate material Fast, cost-effective, environmentally friendly High flexibility

I. Plasma treatment of polymers

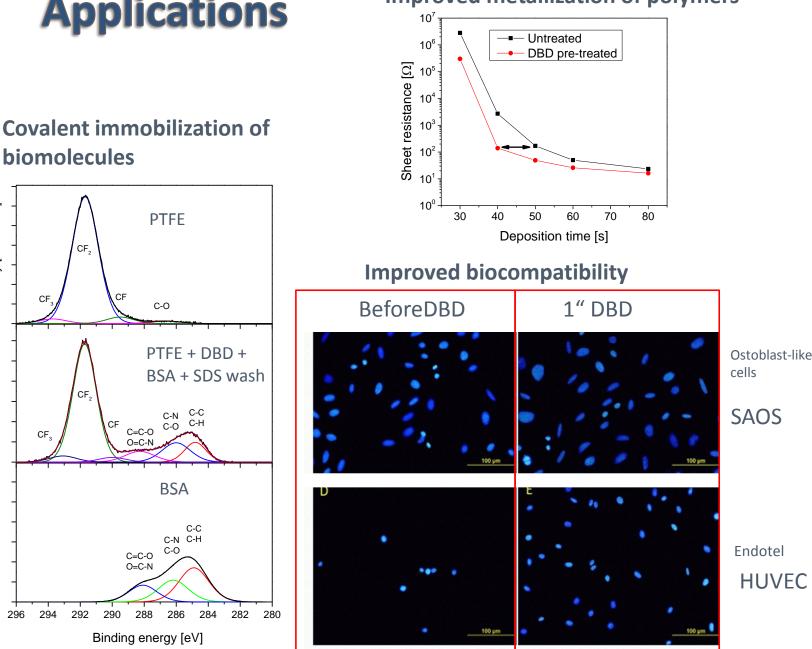


DBD plasma may change surface energy, chemical composition as well as morphology of polymers.



Applications

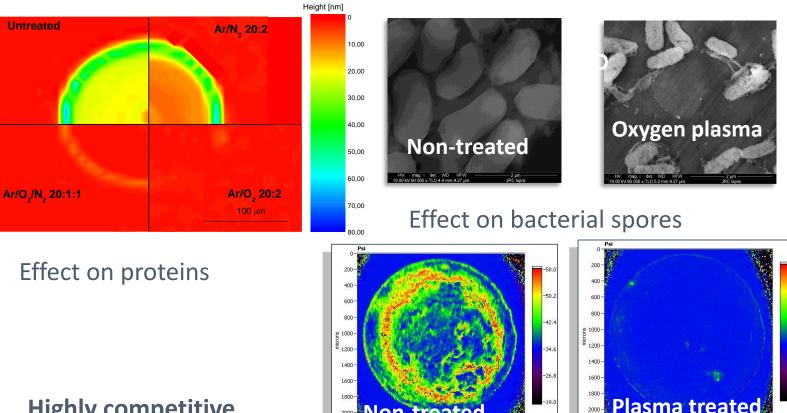
Improved metallization of polymers



3 days after seeding

II. Plasma based sterilization

By means of plasma it is possible to sterilize/decontaminate surfaces.



2000 -2161 -

Highly competitive with other sterilization methods!!!

Effect on endotoxins

2000

200

42.4

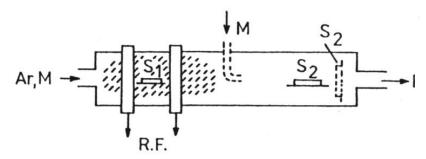
-26.8

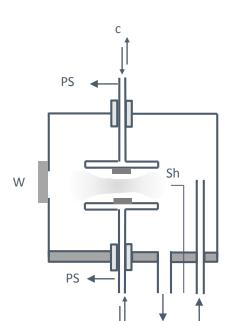
1000 1200 1400 1600 1800

O.Kylián et. al. J.Phys.D: Appl. Phys 41, 2008, Art. No 095201 Kylian and Rossi . Phys. D: Appl. Phys. 42 (2009) 085207 Kylian et.al. Plasma Process. Polym. 2011, 8, 1137 Fumagalli et. al. J. Phys. D: Appl. Phys. 45 (2012)

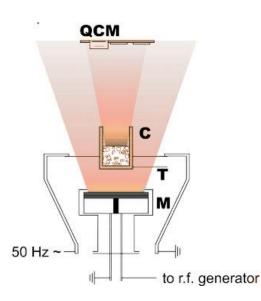
III. Thin films deposition

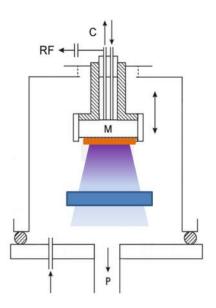
Plasma may be used for deposition of thin films of metals, metal-oxides as well <u>as plasma polymers</u>.

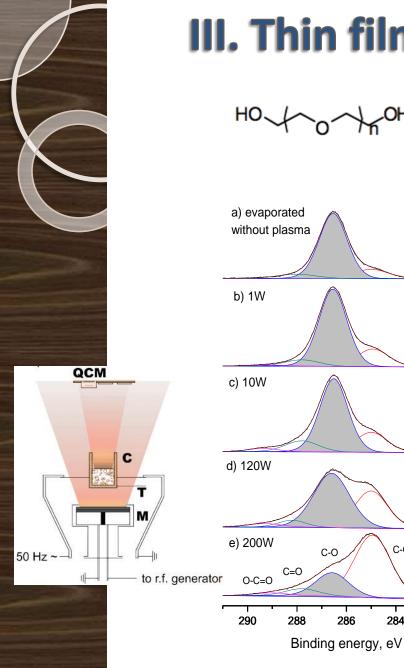




M

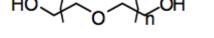






III. Thin films deposition - examples

Non-fouling PEO-like thin films



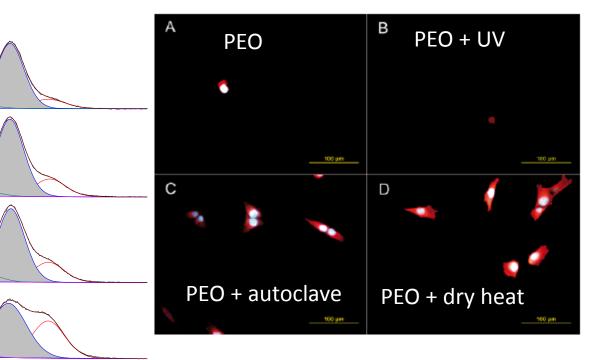
С-С. С-Н

282

284

C-0

286

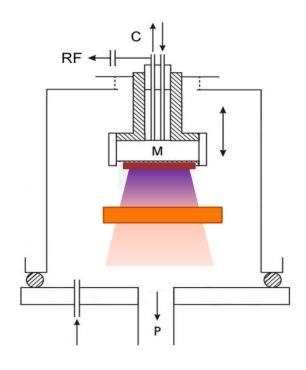


It is possible to fabricate non-fouling PEOlike coatings that withstand UV light sterilization.

A. Choukourov et al. Plasma Process. Polym. 2012, 9, 48 A. Artemenko et. al. Thin Solid Films 2012, 520, 7115

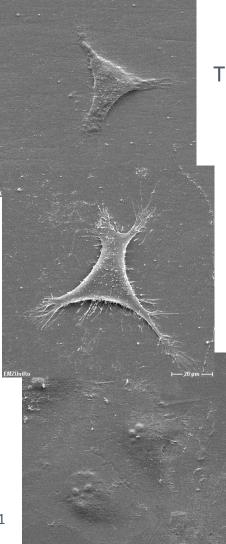
Thin films deposition - examples

Amino-rich thin films



It is possible to fabricate coatings that promote cells growth.

O. Kylian et al. J. Phys. D. Appl. Phys. 2009, 42, 142001 A. Artemenko et. al. Surf. Coat. Tech. 2011, 205, S529

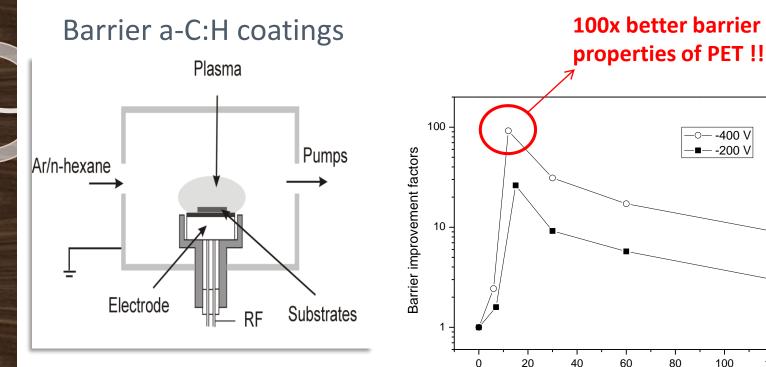


TiAlV

TiAlV + Nylon sputtered in Ar

TiAlV + Nylon sputtered in mixture nitrogen-hydrogen

Thin films deposition - examples



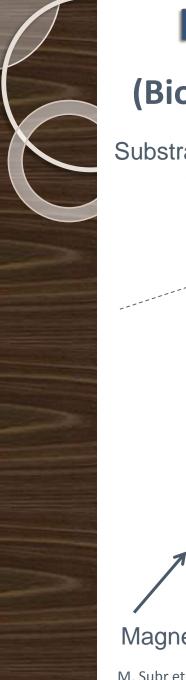


Thin a-C:H films may significantly improve barrier properties of polymeric foils.

Thickness [nm]

120

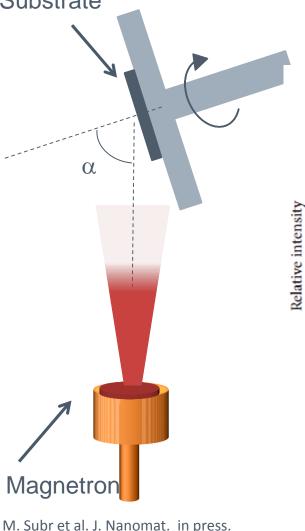
O. Polonskyi et al. Thin Solid Films 2013, 540, 65

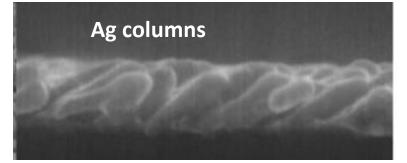


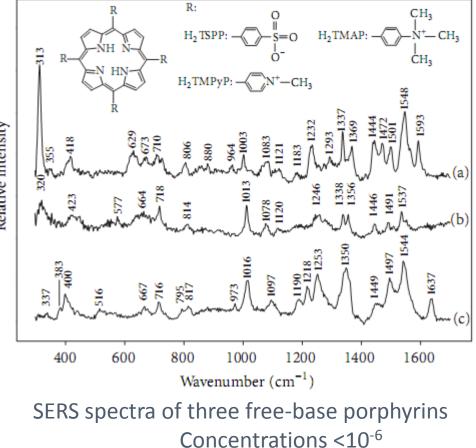
III. Thin films deposition - examples

(Bio)sensing

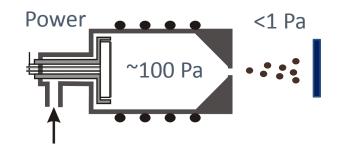
Substrate







IV. Fabrication of nanoparticles



Gas inlet

Pt

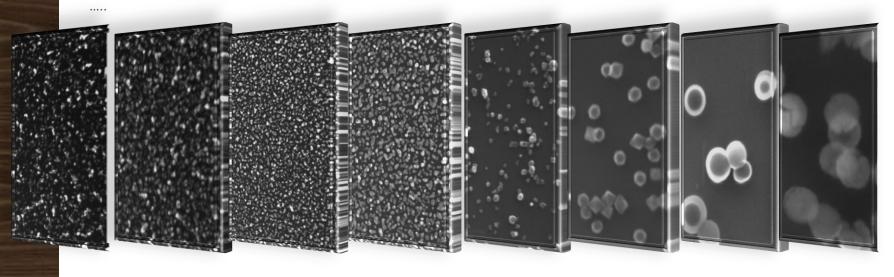
Cu

Solar et al. Surface Coat. Technol. 2011, 205, S42 Drabik et al., Plasma Proces Polym, 2011, 7, 544 Kylian et al., Material Letters 2012, 79, 229 Polonskyi et al., J. Phys D. Appl. Phys. 2012, 45, 495301 Kylian et al. Thin Solid Films 2014, 550, 46 Solar et al. Vacuum 2015, 111, 124

Ag



C:H:N



Au

Ti

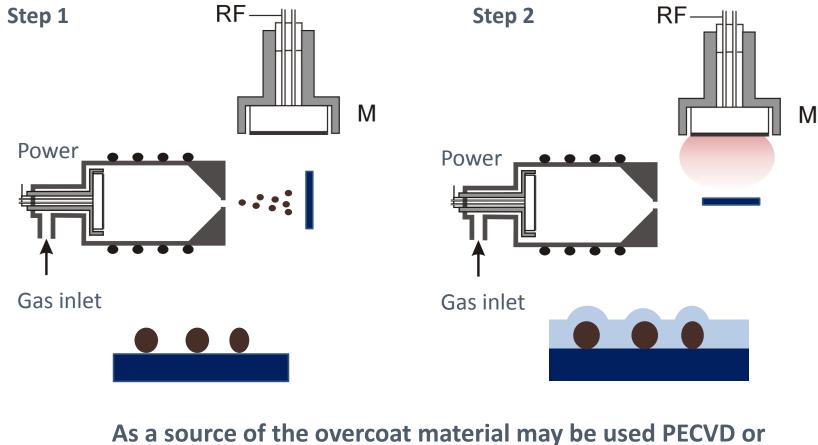
Α

C:H



V. Nanostructured coatings prepared by means of gas aggregation sources

Overcoating nanoparticles by plasma polymer

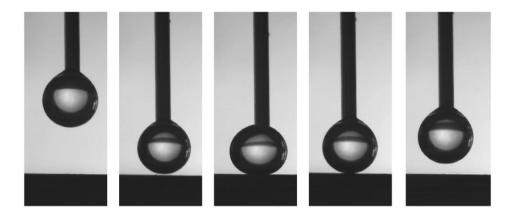


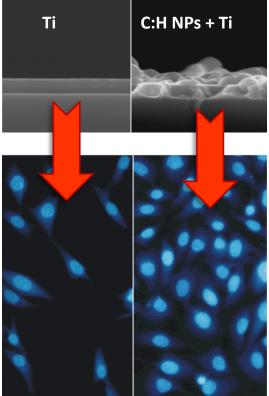
magnetron sputtering.

V. Nanostructured coatings prepared by means of gas aggregation sources

It is possible to control independently surface roughness and surface chemical composition.

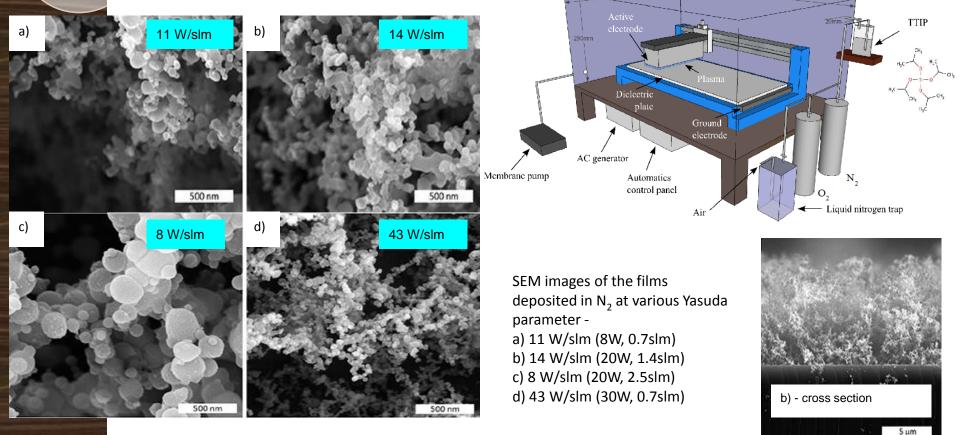
We can prepare nanorough surfaces e.g. for faster osseo-integration or water repellent character





Atmospheric pressure processes: deposition

- dielectric barrier discharge (typical):
 - 20 W, 23 kHz, 15 kVPP, substrate(glass) -electrode gap 1.5 mm
 - monomer: titanium tetraisopropoxide (TTIP), 0.5 mass% in gas (N₂, air)
 - gas flow: 0.7-2.5 slm



• A. Shelemin, A. Choukourov, J. Kousal, D. Slavinska, H. Biederman: Nitrogen-Doped TiO2 Nanoparticles and Their Composites with Plasma Polymer as Deposited by Atmospheric Pressure DBD, PLASMA PROCESSES AND POLYMERS 11, 9 (2014) 864-877



Conclusions

Plasma is versatile tool for surface modification and for deposition of thin functional coatings.

By means of plasma it is possible to tailor surface properties of solid objects.

Possible applications include:

- Biomedical applications
- (Bio)sensors
- Barrier coatings
- Surfaces with controllable wettability etc.



Thank you for your attention.

